

Ink L – Technical data

Spin-coating curve – Ellipsometric Measurements

Experimental:

- *Substrate:* [100] n-doped Silicon, 4 in. wafers ; used as received.
- *Coating:* dispense 4 to 6 mL of InkL onto the wafer, spin at given speed with acceleration set at 1000 rpm.s⁻¹ during 90 to 120 seconds.
- *Soft bake:* 80°C- 3 minutes after spin-coating Ink L onto the substrates.
- *Ellipsometric spectroscopy:* reflection mode with a phase modulated spectroscopic ellipsometer (UVISEL, from Horiba Scientific) on the spectral range 200-800 nm.

Technical Results:

Spin speed (rpm)	700	1000	1500	2000	4000
Mean Thickness (nm)	1098	655	566	521	620

